

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHEN et al.

Atty. Ref.: 2476-37; Confirmation No. 2846

Appl. No. 10/730,381

TC/A.U. 2815

Filed: 09 December 2003

Examiner: Jackson Jr., Jerome

For: PROGRAMMABLE PHOTOLITHOGRAPHIC MASK BASED ON
SEMICONDUCTOR NANO-PARTICLE OPTICAL MODULATORS

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July 23, 2008

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT AFTER FINAL REJECTION

Responsive to the Official Action dated January 23, 2008 (for which petition is hereby made for any necessary extension of time), please amend the above-identified application as follows: